IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

<u>In re</u> application of:) Examiner: Not Yet Assigned
Name Neil M. Mackie et al) Art Group: Not Yet Assigned
Serial No. Not Yet Assigned	Att. Docket No.: MAT-12CIP
Filed: March 17, 2004) Date: March 17, 2004
For: EFFLUENT PRESSURE CONTROLFOR USE IN A PROCESSING SYSTEM)) _)
CERTIFICATE OF MAILING I hereby certify that this correspondence is envelope addressed to: Commissioner of Patents, P.O. Box 1450, Alexandria	Signed: A H
Commissioner of Patents	Jay R Beyer

Commissioner of Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

Enclosed is a form 1449 including references cited in the parent application serial number 10/413,507 filed April 14, 2003 associated with this application. Copies of the references cited in the parent application may be found in the parent application. It is respectfully requested that the cited documents be considered and that the enclosed copies of the forms be initialed by the Examiner to indicate such consideration and a copy thereof returned to applicant(s).

Pursuant to 37 C.F.R. § 1.97, the submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made and is not to be construed as an admission that the information cited in this statement is material to patentability.

Pursuant to 37 C.F.R. § 1.97, this Information Disclosure Statement is being submitted under one of the following (as indicated by an "X" to the left of the appropriate paragraph):

X 37 C.F.R. §1.97(b).
37 C.F.R. §1.97(c). If so, then enclosed with this Information Disclosure Statement is one of the following:
A certification pursuant to 37 C.F.R. §1.97(e) or
A check for \$ for the fee under 37 C.F.R. § 1.17(p).
37 C.F.R. §1.97(d). If so, then enclosed with this Information Disclosure Statement are the following:
(1) A certification pursuant to 37 C.F.R. §1.97(e);
(2) A petition requesting consideration of the Information Disclosure Statement; and
(3) Please charge Deposit Account No. 19-1685 (Order No. MAT-12CIP) \$ for the fee under
37 C.F.R. §1.17(i) for submission of the Information Disclosure Statement. (a duplicate copy of this sheet is enclosed)

If there are any additional charges, please charge Deposit Account No. 19-1685 (Order No. MAT-12CIP).

Respectfully submitte

Jay R Beyer

Registration No. 39,907

Form 1449 (Modified)

Information Disclosure

Atty Docket No.

MAT-12CIP

Serial No.:

Not Yet Assigned

Statement By Applicant

Applicants:
Neil M. Mackie et al

Filing Date

(Use Several Sheets if Necessary)

March 17, 2004

Group
Not Yet Assigned

U.S. Patent Documents

Examiner						Sub-	Filing
Initial	No.	Patent No.	Date	Patentee	Class	class	Date
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	В	4,413,022	11/1/83	Suntola et al		-	
	С	4,798,165	1/17/89	deBoer et al			
	D	5,006,363	4/9/91	Fujii et al			
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	G	5,648,321	7/15/97	Bednorz et al			·
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	M	5,964,949	10/12/99	Savas			
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Foreign Patent or Published Foreign Patent Application

Examiner		Document	Publication	Country or		Sub-	Transla	tion
Initial	No.	No.	Date	Patent Office	Class	class	Yes	No
	PP							

Other Documents

Examiner						
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	QQ	D. Park et al, SiON/Ta2O5/TiN Gate Stack Transistor with 1.8nm Equivalent SiO2 Thickness, 1998, Tech Dig Int Electron Device Meet, P 381				
	RR	Laun et al, Ultra Thin High Quality Ta2O5 Gate Dielectric Prepared By In Situ Rapid Thermal Processing, 1999, Tech Dig Int Electron Device Meet, 4 Pages				
	SS	Wilk et al, Hafnium and Zirconium Silicates for Advanced Gate Dielectrics, 2000, Journal of App Physics, Vol 87(1), pp 484-492				
	TT	Wilk et al, Stable Zirconium Silicate Gate Dielectrics Deposited Directly on Silicon, 1999, Applied Physics Letters, 76(1), pp 112-114				
	UU	Denis et al, Model to Simulate Parabolic Followed by Linear Oxidation Kinetics, 1988, Oxideation Metals, pp 153-167				
	VV	Schuisky et al, Atomic Layer Chemical Vapor Deposition of TiO2 Low Temperature Epitaxy of Rutile and Anatase, 2000, Journal of The Electrochemical Society, Vol 147(9), pp 3319-3325				
	WW	PCT Search Report, 7/24/03				
	XX	Buchan et al, Epitaxial Growth of GaAs with (C2H%)2GaCl and AsH3 in a Hot-Wall System, 1991, Journal of Crystal Growth 107, pp 331-336				
	YY	Higashi et al, Sequential Surface Chemical Reaction Limited Growth of High Quality Al2O3 dielectrics				
Examiner		Date Considered				
-						

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.